

## **AMENDMENTS TO THE CLAIMS**

*The listing of claims will replace all prior versions and listings of claims in the application:*

### **Listing of Claims:**

1.     **(Previously Presented)**     A variable adaptive mask for use with a physical vapor deposition process, comprising:
  - a fixed mask portion that comprises a top layer and a bottom layer;
  - a plurality of channels extending through the fixed mask portion;
  - a first plurality of wires positioned on the bottom layer, each wire of the first plurality of wires being disposed in a substantially spiral arrangement about a respective channel;
  - a second plurality of wires positioned on the top layer, each wire of the second plurality of wires being disposed in a substantially spiral arrangement about a respective channel; and
  - means for mounting the mask in a fixed position relative to a solid target material and a substrate.
2.     **(Canceled)**
3.     **(Original)**     The mask of claim 1, wherein the channels have a circular profile.
4.     **(Original)**     The mask of claim 1, wherein the channels have a rectangular profile.
5.     **(Canceled)**

6.     **(Previously Presented)**     The mask of claim 1, wherein the wires generate a magnetic field in the channels when electrical current is passed through the wires.

7.     **(Currently amended)**     The mask of claim ~~[[1]]6~~, wherein the wires are electrically connected to a computer or integrated circuit such that the magnetic field can be precisely controlled.

8.     **(Original)**     The mask of claim 1, further comprising a hard ferromagnetic material placed within the channels.

9.     **(Withdrawn)** The mask of claim 1, wherein the means for controlling throughput comprises strips of material adjacent to the channels and having a high coefficient of thermal expansion such that the material reacts to heat by expanding.

10.    **(Original)**     The mask of claim 1, wherein the means for mounting comprises at least one mounting hole in the fixed mask portion.

11.    **(Original)**     The mask of claim 1, further comprising a calibration scale on the fixed mask portion.

12. **(Currently amended)** A variable adaptive mask for use with a physical vapor deposition process, comprising:

- a fixed mask portion including a calibration scale;
- a plurality of channels extending through the fixed mask portion;
- a plurality of wires positioned on the fixed mask portion, each wire of the plurality of wires being disposed in a substantially spiral arrangement about a respective channel; and
- one or more mounting holes for mounting the mask in a fixed position relative to a solid target material and a substrate.

13. **(Original)** The mask of claim 12, wherein the channels are defined by a top layer and a bottom layer of the fixed mask portion.

14. **(Cancelled)**

15. **(Previously Presented)** The mask of claim 12, wherein the wires generate a magnetic field in the channels when electrical current is passed through the wires.

16. **(Currently amended)** The mask of claim ~~[[12]]~~15, wherein the wires are electrically connected to a computer or integrated circuit such that the magnetic field can be precisely controlled.

17. **(Original)** The mask of claim 12, further comprising a hard ferromagnetic material placed within the channels.

18. **(Cancelled).**

19. **(Withdrawn)** A variable adaptive mask for use with a physical vapor deposition process, comprising:
  - a fixed mask portion;
  - a plurality of channels extending through the fixed mask portion;
  - a thermal control mechanism configured to control throughput of a vaporized target material through the channels; and
  - one or more mounting holes for mounting the mask in a fixed position relative to a solid target material and a substrate.
20. **(Withdrawn)** The mask of claim 19, wherein the channels have a rectangular profile.
21. **(Withdrawn)** The mask of claim 19, wherein the thermal control mechanism comprises strips of material adjacent to the channels and having a high coefficient of thermal expansion such that the material reacts to heat by expanding.
22. **(Withdrawn)** The mask of claim 19, further comprising a calibration scale on the fixed mask portion.

23.       **(Withdrawn)** A method of controlling a physical vapor deposition process, comprising:  
providing a variable adaptive mask comprising:  
    a fixed mask portion;  
    a plurality of channels extending through the fixed mask portion; and  
    a magnetic control mechanism configured to control throughput of a vaporized target material through the channels;  
generating a magnetic field in the channels;  
directing vaporized target material particles toward the channels such that the particles are affected by the magnetic field which causes a portion of the particles to bend away from a central portion of the channels toward an edge of the channels, wherein the throughput of the vaporized target material particles is proportional to the magnitude of the magnetic field.

24.       **(Withdrawn)** The method of claim 23, wherein the magnetic control mechanism comprises wires wrapped in a spiral configuration around each of the channels.

25.       **(Withdrawn)** The method of claim 24, wherein the wires generate the magnetic field in the channels when electrical current is passed through the wires.

26.       **(Withdrawn)** The method of claim 24, wherein the wires are electrically connected to a computer or integrated circuit such that the magnetic field can be precisely controlled.

27.       **(Withdrawn)** A method of controlling a physical vapor deposition process, comprising:

      providing a variable adaptive mask comprising:

          a fixed mask portion;

          a plurality of channels extending through the fixed mask portion; and

          a thermal control mechanism configured to control throughput of a vaporized target material through the channels; and

      directing vaporized target material particles toward the channels, wherein the throughput of the vaporized target material particles is proportional to the heat applied to the adaptive mask.

28.       **(Withdrawn)** The method of claim 27, wherein the thermal control mechanism comprises strips of material adjacent to the channels and having a high coefficient of thermal expansion such that the material reacts to heat by expanding.